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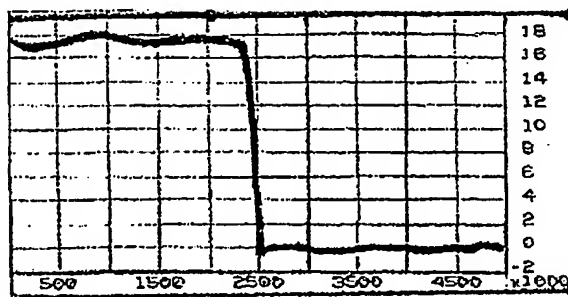
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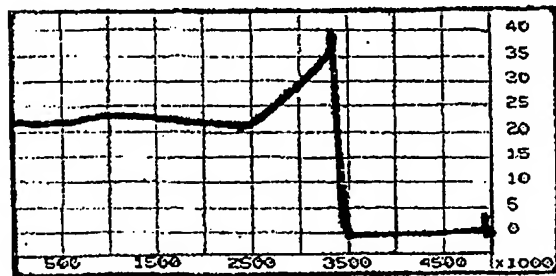
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(54) Title: **A CLEANING AGENT COMPOSITION FOR A POSITIVE OR A NEGATIVE PHOTORESIST**



Composition of examples 1 and 2



Composition of comparative example 1

\* X axis: Distance from the cleaned area (unit: 1nm).

\* Y axis: Height of the photoresist coating (unit: 0.1μm)

(57) Abstract: The present invention relates to a composition for cleaning a photoresist and is to provide a cleaning composition wherein the residue of the photoresist does not remain on the boundary surface between the cleaned area and the not-cleaned area after a negative photoresist containing pigment is cleaned, soft-baked, exposed and developed. The present invention provides a composition for cleaning a positive or negative photoresist which comprises (a) from 0.1 to 20 wt.% of and alkyl oxide polymer with a molecular weight of from 50 to 2000 and (b) from 80 to 99.9 wt.% of an organic solvent comprising: (b-1) from 1 to 20 parts by weight of dipropylene glycol methyl ether (DPGME), from 10 to 50 parts by weight of N-methyl pyrrolidone (NMP) and from 50 to 90 parts by weight of methyl isobutyl ketone (MIBK), or (b-2) from 10 to 90 parts by weight of dimethyl formaldehyde (DMF) or dimethylacetamide (DMAc) and from 10 to 50 parts by weight of n-butyl acetate.

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